

SUPPORTING INFORMATION FOR:

Two-Photon Absorption in a Conformationally Twisted D- π -A Oligomer : A Synergic Photosensitizing Approach for Multiphoton Lithography

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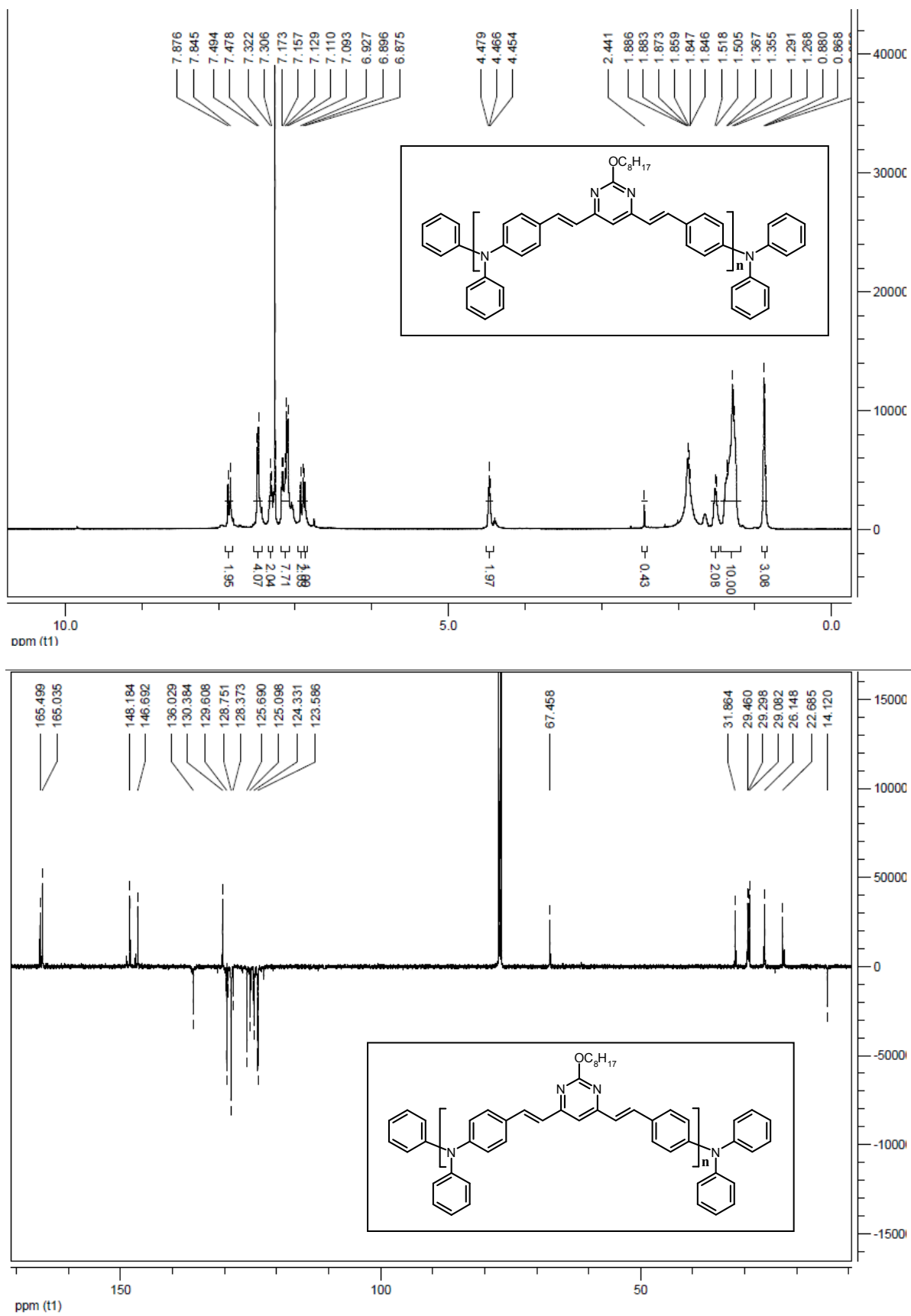


Figure S1.

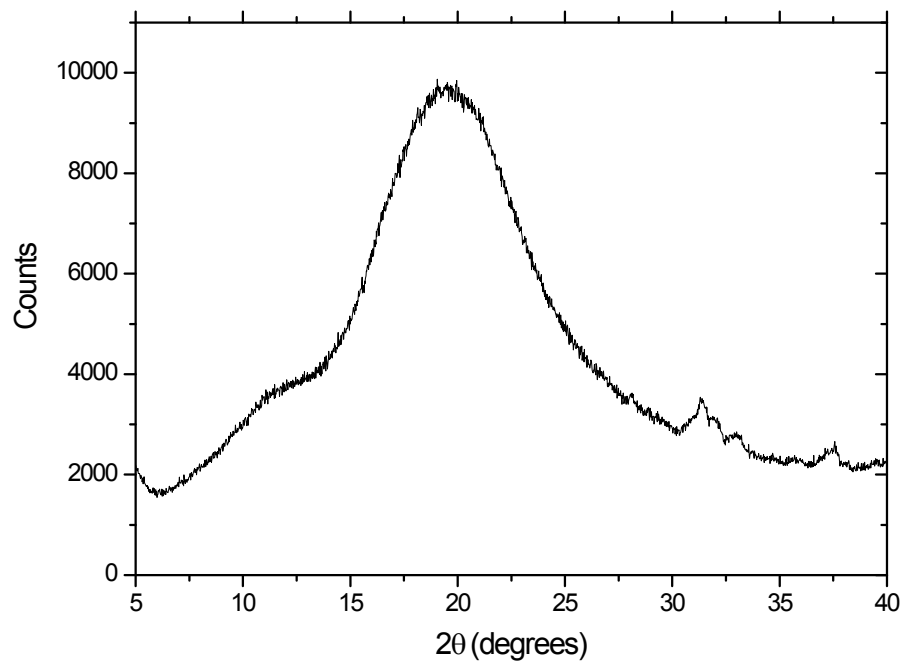


Figure S2.

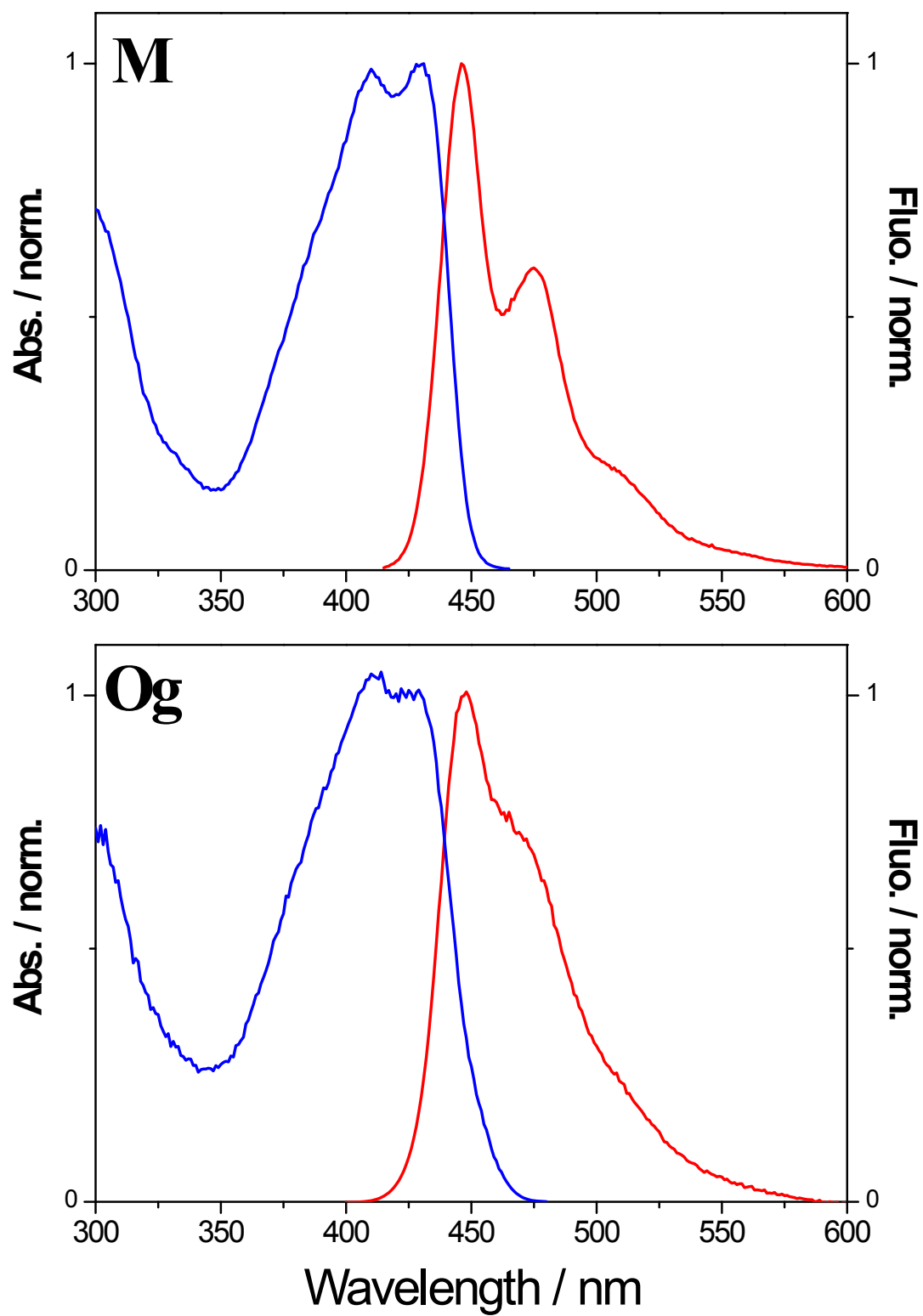


Figure S3.

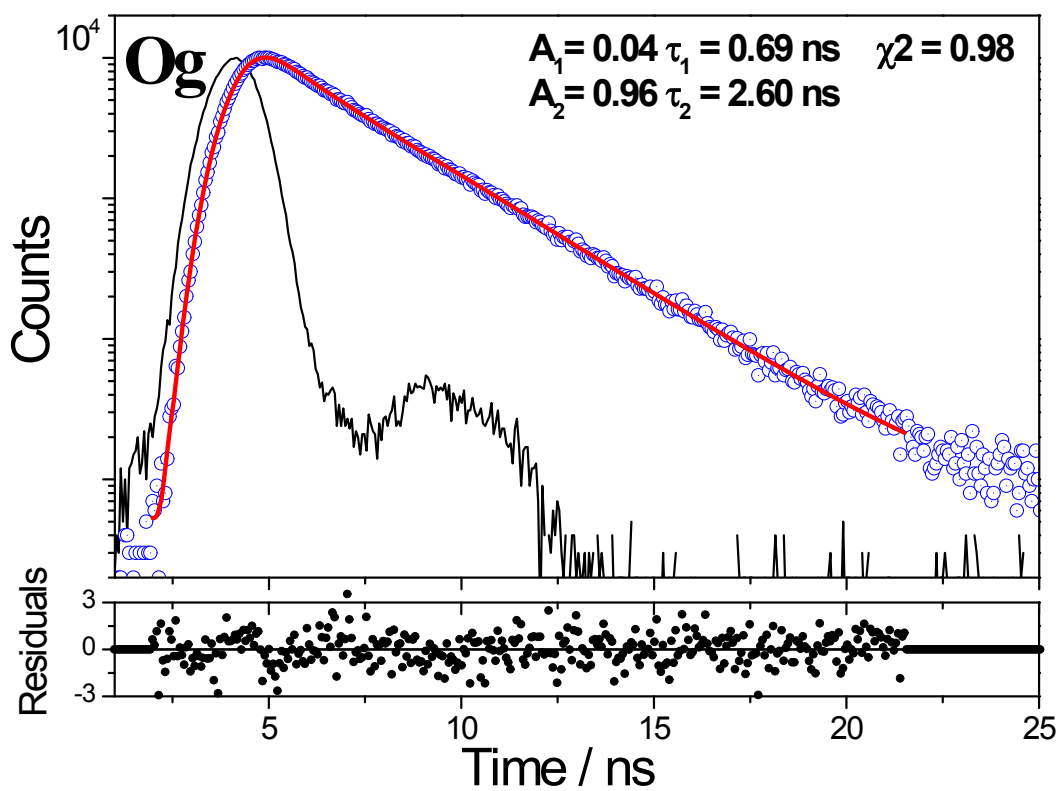
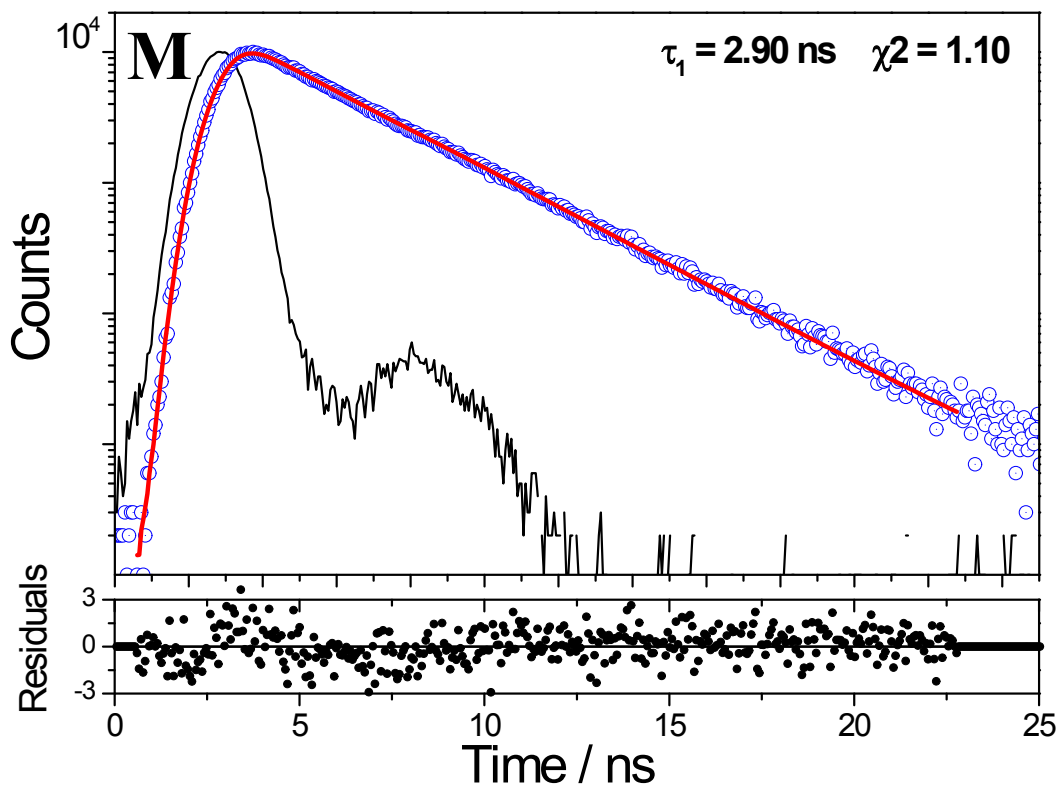


Figure S4.

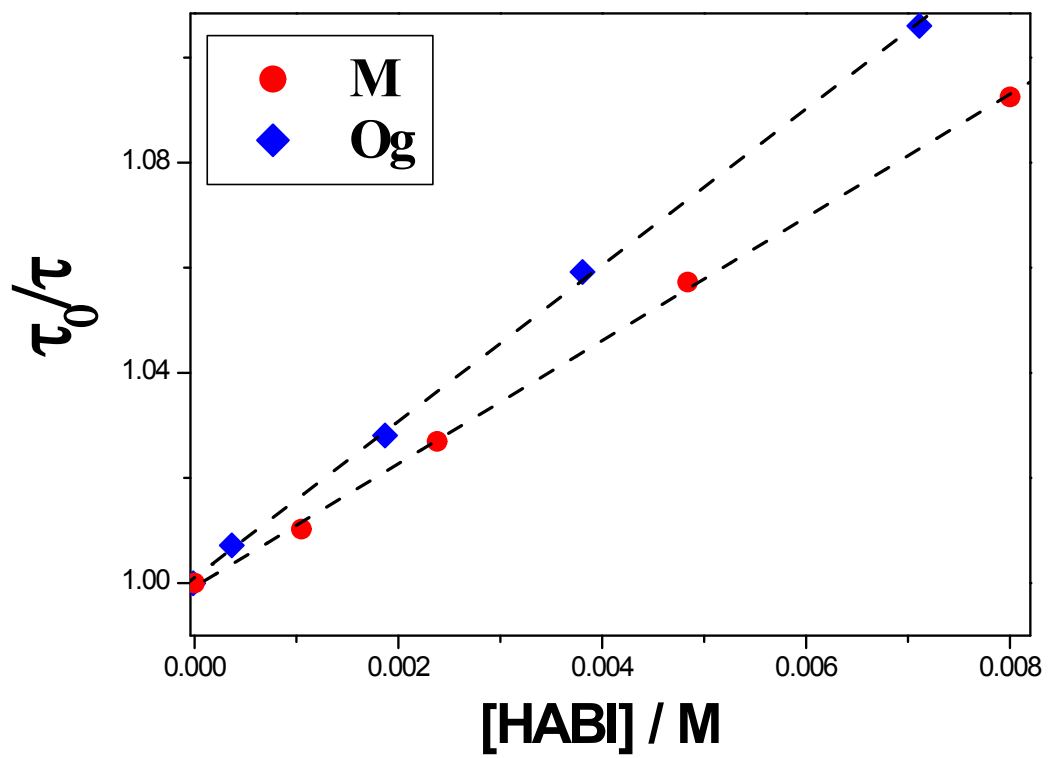


Figure S5.